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(54) Title: DEVICE MANUFACTURING METHOD AND DEVICE

(57) Abstract: A method for patterning a polished silicon surface is disclosed, the method comprising steps leading to an organic monolayer on at least a part of the silicon surface, the monolayer being functionalised in specific desired locations. The method can be used to produce a device comprising one or more FET structures, the gate of the FET being formed by the functionalised organic monolayer. The functionalised monolayer preferably contains oligosaccharides or oligopeptides which are capable of interacting with biological substance, such that the device acts as a bio-sensor.

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(54) Title: BIOSENSOR AND METHOD OF PREPARATION

(57) Abstract: A method for patterning a polished silicon surface is disclosed, the method comprising steps leading to an organic monolayer on at least a part of the silicon surface, the monolayer being functionalised in specific desired locations. The method can be used to produce a device comprising one or more FET structures, the gate of the FET being formed by the functionalised organic monolayer. The functionalised monolayer preferably contains oligosaccharides or oligopeptides which are capable of interacting with biological substance, such that the device acts as a bio-sensor.

